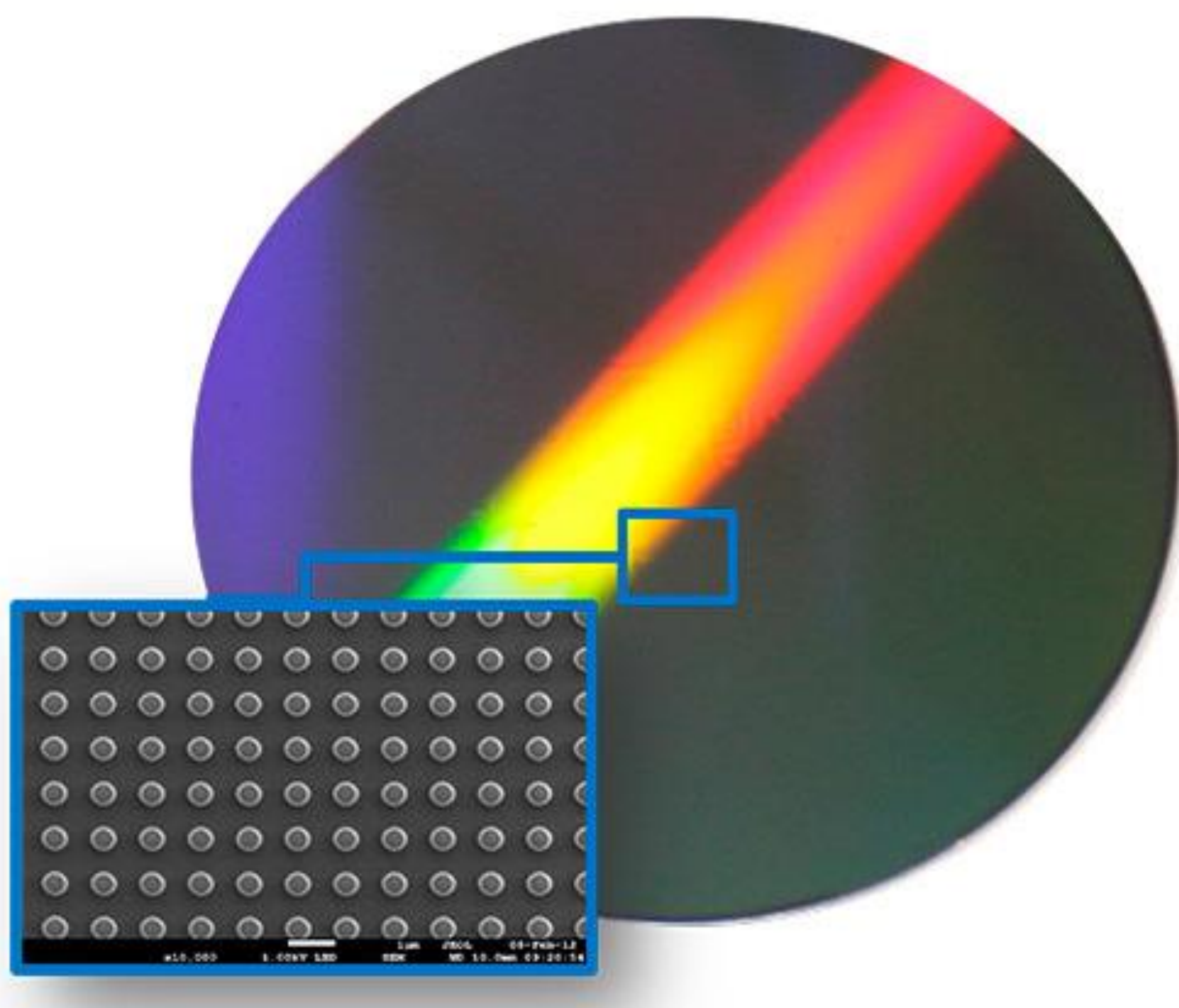


# AGING OF MATERIALS AND THEIR IMPACT ON THE NANOIMPRINT LITHOGRAPHY PROCESS

## Project team

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## Goals of the project

- Which one of the three materials exhibits the best properties?
- Are there any mechanical or chemical changes of the workingstamp due to the repeated UV-light exposure?
- How is the process affected by a rising number of imprints?

## Analysis and findings

- ✓ UV/AF1 fits best
- ✓ No distinct property changes due to aging
- ✓ Limiting factor for the maximum possible number of imprints is the peel-force

